PVD Magnetron Sputtering Service

The Challenge

Conducting test sputtering while developing a new product can be expensive and time consuming, especially when working with precious metals. Given the time and resources needed to set up a short run, a developer may not have the proper sputtering equipment and/or materials to ensure accurate testing during the research and development phase.

The Solution

Materion offers an in-house PVD Magnetron Sputtering Service to assist our customers. With our extensive knowledge and experience, state-of-the-art equipment and high-quality materials, we are the perfect partner to support new product research and development.

Benefits of this service include:
- Zero interruption to current production
- Elimination of time spent reconfiguring and/or cleaning a vacuum chamber
- Material testing before purchasing full size sputtering targets
- Custom pricing based on sputtering target supplier and target material
- Assistance from Materion product development experts

Available Deposition Options
- Static or dynamic deposition
- Metallic or reactive sputtering
- Gas options: Ar, O2, N2, Ar/H2
- DC-etching
- Substrate heating up to 400°C

Depending on material, options include coating of a triple stack system without any vacuum break in PK75 & PK500 configuration.

Tool Configuration Types
- Dual rotatable, length: 500mm, DC-single or MF-dual mode
- 3x PK500 Planar Targets, length x width: 488mm x 88mm, DC-single mode
- 3x PK75 Planar Targets, Ø 75mm, DC-single or RF mode

Power Supply Options
- DC or DC pulsed-mode:
  - AE Pinnacle+, 20kW
  - MF-mode: Hüttinger TIG20, 20kW (for dual rotatable only)
  - RF-mode: Hüttinger PFG1000, 1kW (for one PK75 only)

To request a custom quote, visit materion.com/spattering-service